

ABSTRACT

Provided are a chromium-silicon alloy sputtering target material and a preparation method thereof. The preparation method includes the following steps: (1) filling chromium-silicon alloy powder having a target mass proportion into a mold, sealing the mold, and compacting the mold by vibration; (2) degassing the mold compacted in step (1); (3) subjecting the mold degassed in step (2) to hot isostatic pressing treatment at a temperature of 1000 °C to 1350 °C to obtain a crude chromium-silicon alloy sputtering target material; and (4) machining the crude product to obtain the chromium-silicon alloy sputtering target material.

Figure 1